

L Number	Hits	Search Text	DB	Time stamp
5	12	Hirae and controller and clean\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/07 09:12
4	12	Hirae and Sadao and Sato and Masanobu and Yasuda and Shuichi	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/07 09:12
-	0	fushimi-ku.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/22 10:07
-	0	fushimiku.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 14:02
-	2812	fushimi.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 14:02
-	1	"fushimi-ku" and sadao and masanobu and yasuda	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 14:04
-	338139	Hirae Sadao Sato Masanobu Yasuda Shuichi	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/11 15:14
-	1490	(Hirae Sadao Sato Masanobu Yasuda Shuichi ) and ozone	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 14:06
-	237	((Hirae Sadao Sato Masanobu Yasuda Shuichi ) and ozone) and ultraviolet	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 14:06
-	93	((Hirae Sadao Sato Masanobu Yasuda Shuichi ) and ozone) and ultraviolet and clean\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 14:07
-	27	((Hirae Sadao Sato Masanobu Yasuda Shuichi ) and ozone) and ultraviolet and clean\$4 and wafer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 14:13
-	0	degendt and ultraviolet and ozone and clean\$4 and wafer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 14:14
-	3	degendt	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 14:36
-	84151	dainippon.as.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 14:36





	3	photoresist near applicator and chuck and spin\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/06/22 10:09
	4	photoresist near12 applicator and chuck and spin\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/06/22 10:09
	1713	photoresist and chuck and spin\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/06/22 10:10
	513	photoresist and chuck and spin\$4 and ultraviolet	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/06/22 10:10
	224	photoresist and chuck near12 spin\$4 and ultraviolet	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/06/22 10:35
	1	"4749440".PN.	USPAT	2004/06/22 10:15
	1	"4765866".PN.	USPAT	2004/06/22 10:15
	1	"4778532".PN.	USPAT	2004/06/22 10:16
	1	"4778532".PN.	USPAT	2004/06/22 10:16
	1	"4816098".PN.	USPAT	2004/06/22 10:16
	1	"4904338".PN.	USPAT	2004/06/22 10:17
	1	"4931103".PN.	USPAT	2004/06/22 10:17
	187	chuck near12 spin\$4 and (UV ultraviolet) and (dispens\$4 coat\$3) and nozzle	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/06/22 10:36
	217	chuck near12 spin\$4 and (UV ultraviolet) and (dispens\$4 coat\$3) and nozzle	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/06/22 10:37
	1	"5626913".PN.	USPAT	2004/06/22 10:44
	1	"5625433".PN.	USPAT	2004/06/22 10:44
	1	"5252137".PN.	USPAT	2004/06/22 10:44
	1	"4824763".PN.	USPAT	2004/06/22 10:44
	3	"5910420"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/06/23 11:23
	4	(("5464480") or ("6403498")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/05 12:35
	0	controller near22 spin adj coat near33 (ultra\$violet UV)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/07 06:49
	0	controller near22 spin adj coat near33 (cure ultra\$violet UV)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/07 06:49
	0	controller near22 spin adj coat and (cure ultra\$violet UV)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/07 06:50

	1	controller near22 spin adj coat	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/07/07 06:50
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(1) "4816098".PN.  
 (1) "4904338".PN.  
 (1) "4931103".PN.  
 (187) chuck near12 spin\$4 and  
 (217) chuck near12 spin\$4 and  
 (1) "5626913".PN.  
 (1) "5625433".PN.  
 (1) "5252137".PN.  
 (1) "4824763".PN.  
 (3) "5910420"  
 (4) ("5464480") or ("6403498")  
 (0) controller near22 spin adj  
 (0) controller near22 spin adj  
 (0) controller near22 spin adj  
 (1) controller near22 spin adj

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Tagged (10)

DBs: USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM, TDB  Plurals  Highlight all hit terms initially  
 Default operator: OR

	U	I	Document ID	Issue Date	Pages	Title	Current OR	Current XRef	Retrieval Classifi	Ir
1	<input type="checkbox"/>	<input checked="" type="checkbox"/>	US 20010001392	20010524	13	Substrate treating method and apparatus	134/1.3	156/345.11		Hirae, al.
2	<input type="checkbox"/>	<input checked="" type="checkbox"/>	US 4161356 A	19790717	8	Apparatus for in-situ processing of photoplat	396/625	134/149; 134/153;		Giffin, et al.
3	<input type="checkbox"/>	<input checked="" type="checkbox"/>	US 5078832 A	19920107	22	Method of treating wafer surface	216/94	134/1; 134/3;		Tanaka,
4	<input type="checkbox"/>	<input checked="" type="checkbox"/>	US 5288333 A	19940222	25	Wafer cleaning method and apparatus therefore	134/31	134/11; 134/12;		Tanaka, al.
5	<input type="checkbox"/>	<input checked="" type="checkbox"/>	US 5634980 A	19970603	11	Method for washing substrates	134/3	134/18; 134/33; 134/	18	Tomita, al.
6	<input type="checkbox"/>	<input checked="" type="checkbox"/>	US 5669979 A	19970923	41	Photoreactive surface processing	134/1	134/1.1; 134/1.2;	134/1; 134/1.	Elliott et al.
7	<input type="checkbox"/>	<input type="checkbox"/>	US 5843527 A	19981201	60	Coating solution applying method and app	427/240	427/385.5; 438/782		Sanada,
8	<input type="checkbox"/>	<input checked="" type="checkbox"/>	US 5966635 A	19991012	9	Method for reducing particles on a substrat		134/104.1; 134/153;		Hiatt, al.
9	<input type="checkbox"/>	<input checked="" type="checkbox"/>	US 5975098 A	19991102	37	Apparatus for and method of cleaning subs	134/148	134/153; 134/181;		Yoshita Mitsuak
10	<input type="checkbox"/>	<input checked="" type="checkbox"/>	US 6491452 B2	20021210	10	Developing method and developing apparatus	396/611	118/52; 427/240		Konishi al.